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The listing of claims will replace all prior versions, and listings, of claims in the application:

## **Listing of Claims:**

1. (Withdrawn) A bootstrap circuit comprising a thin film transistor wherein:

a channel forming region of the thin film transistor comprises a polycrystalline semiconductor, and

the thin film transistor is a depletion mode transistor.

- 2. (Withdrawn) The bootstrap circuit according to claim 1, wherein the thin film transistor is directly connected to an output terminal.
- (Withdrawn) The bootstrap circuit according to claim 1, wherein the polycrystalline semiconductor film is provided over either a quartz substrate or a glass substrate.
  - 4. (Withdrawn) A bootstrap circuit comprising a thin film transistor wherein:
- a channel forming region of the thin film transistor comprises a polycrystalline semiconductor which is formed by crystallizing an amorphous silicon, and the thin film transistor is a depletion mode transistor.
  - 5. (Withdrawn) The bootstrap circuit according to claim 4, wherein the thin film transistor is directly connected to an output terminal.
  - 6. (Withdrawn) The bootstrap circuit according to claim 4,

wherein the polycrystalline semiconductor film is provided over either a quartz substrate or a glass substrate.

7. (Currently Amended) A driver circuit comprising:

a shift register;

a buffer circuit electrically connected to the shift register, comprising a source follower circuit comprising a thin film transistor; and

an analog memory electrically connected to the buffer circuit,

wherein:

a channel forming region of the thin film transistor comprises a polycrystalline semiconductor,

the thin film transistor is a depletion mode transistor, and

an impurity is doped to a channel forming region of a semiconductor layer of the thin film transistor comprises a metal element which is capable of promoting the crystallization of a semiconductor film at a concentration of 5 x 1012 to 5 x 1014 atoms/cm2.

- 8. (Original) The driver circuit according to claim 7, wherein the thin film transistor is directly connected to an output terminal.
- 9. (Original) The driver circuit according to claim 7, wherein the polycrystalline semiconductor film is provided over either a quartz substrate or a glass substrate.
  - 10. (Currently Amended) A driver circuit comprising:

a shift register;

a buffer circuit electrically connected to the shift register, comprising a source follower circuit comprising a thin film transistor; and

an analog memory electrically connected to the buffer circuit, wherein:

a channel forming region of the thin film transistor comprises a polycrystalline semiconductor which is formed by crystallizing an amorphous silicon,

the thin film transistor is a depletion mode transistor, and

an impurity is doped to a channel forming region of a semiconductor layer of the thin film transistor comprises a metal element which is capable of promoting the crystallization of a semiconductor film at a concentration of  $5 \times 10^{12}$  to  $5 \times 10^{14}$  atoms/cm<sup>2</sup>.

- 11. (Original) The driver circuit according to claim 10, wherein the thin film transistor is directly connected to an output terminal.
- 12. (Original) The driver circuit according to claim 10, wherein the polycrystalline semiconductor film is provided over either a quartz substrate or a glass substrate.
  - 13. (Currently Amended) A driver circuit comprising:

a shift register;

a buffer circuit electrically connected to the shift register, comprising a bootstrap circuit comprising a thin film transistor; and

an analog memory electrically connected to the buffer circuit,

wherein:

a channel forming region of the thin film transistor comprises a polycrystalline semiconductor.

the thin film transistor is a depletion mode transistor, and

an impurity is doped to a channel forming region of a semiconductor layer of the thin film transistor comprises a metal element which is capable of promoting the

crystallization of a semiconductor film at a concentration of 5 x 10<sup>12</sup> to 5 x 10<sup>14</sup> atoms/cm<sup>2</sup>.

- 14. (Original) The driver circuit according to claim 13, wherein the thin film transistor is directly connected to an output terminal.
- 15. (Original) The driver circuit according to claim 13, wherein the polycrystalline semiconductor film is provided over either a quartz substrate or a glass substrate.
  - 16. (Currently Amended) A driver circuit comprising: a shift register;

a buffer circuit electrically connected to the shift register, comprising a bootstrap circuit comprising a thin film transistor; and

an analog memory electrically connected to the buffer circuit, wherein:

a channel forming region of the thin film transistor comprises a polycrystalline semiconductor which is formed by crystallizing an amorphous silicon,

the thin film transistor is a depletion mode transistor, and

an impurity is doped to a channel forming region of a semiconductor layer of the thin film transistor comprises a metal element which is capable of promoting the crystallization of a semiconductor film at a concentration of 5 x 10<sup>12</sup> to 5 x 10<sup>14</sup> atoms/cm<sup>2</sup>.

- 17. (Original) The driver circuit according to claim 16, wherein the thin film transistor is directly connected to an output terminal.
- 18. (Original) The driver circuit according to claim 16,

wherein the polycrystalline semiconductor film is provided over either a quartz substrate or a glass substrate.

19. (Withdrawn) A display device comprising:

an insulating surface;

a signal line over the insulating surface;

a scanning line over the insulating surface;

a pixel electrically connected to the signal line and the scanning line; and

a driver circuit electrically connected to the scanning line, comprising:

a shift register;

substrate or a glass substrate.

a buffer circuit electrically connected to the shift register, comprising a bootstrap circuit comprising a thin film transistor; and

an analog memory electrically connected to the buffer circuit,

wherein:

a channel forming region of the thin film transistor comprises a polycrystalline semiconductor, and

the thin film transistor is a depletion mode transistor.

- 20. (Withdrawn) The display device according to claim 19, wherein the thin film transistor is directly connected to an output terminal.
- 21. (Withdrawn) The display device according to claim 19, wherein the polycrystalline semiconductor film is provided over either a quartz
- 22. (Withdrawn) A display device comprising: an insulating surface; a signal line over the insulating surface;

a scanning line over the insulating surface;

a pixel electrically connected to the signal line and the scanning line; and

a driver circuit electrically connected to the scanning line, comprising:

a shift register;

a buffer circuit electrically connected to the shift register, comprising a bootstrap circuit comprising a thin film transistor; and

an analog memory electrically connected to the buffer circuit,

wherein:

a channel forming region of the thin film transistor comprises a polycrystalline semiconductor which is formed by crystallizing an amorphous silicon, and the thin film transistor is a depletion mode transistor.

- 23. (Withdrawn) The display device according to claim 22, wherein the thin film transistor is directly connected to an output terminal.
- 24. (Withdrawn) The display device according to claim 22, wherein the polycrystalline semiconductor film is provided over either a quartz substrate or a glass substrate.
- 25. (Currently Amended) The driver circuit according to claim 7, wherein the metal element is nickel the semiconductor layer of the thin film transistor comprises a metal element which is capable of promoting the crystallization of a semiconductor film.
- 26. (Currently Amended) The driver circuit according to claim 10, wherein the metal element is nickel the semiconductor layer of the thin film transistor comprises a metal element which is capable of promoting the crystallization of a semiconductor film.

- 27. (Currently Amended) The driver circuit according to claim 13, wherein the metal element is nickel the semiconductor layer of the thin film transistor comprises a metal element which is capable of promoting the crystallization of a semiconductor film.
- 28. (Currently Amended) The driver circuit according to claim 16, wherein the metal element is nickel the semiconductor layer of the thin film transistor comprises a metal element which is capable of promoting the crystallization of a semiconductor film.
- 29. (New) The driver circuit according to claim 25, wherein the metal element is nickel.
- 30. (New) The driver circuit according to claim 26, wherein the metal element is nickel.
- 31. (New) The driver circuit according to claim 27, wherein the metal element is nickel.
- 32. (New) The driver circuit according to claim 28, wherein the metal element is nickel.